UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 6,936,484 B2

Page 1 of 1

DATED

: August 30, 2005

INVENTOR(S) : Masakazu Kanechika et al.

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 46,

Line 20, Claim 16 should read:

-- A method as defined in claim 15, wherein the semiconductor material substrate or layer comprises silicon; the first impurity is oxygen; and the second impurity is boron. --.

Signed and Sealed this

Third Day of January, 2006

JON W. DUDAS
Director of the United States Patent and Trademark Office